Title (en)

METHOD AND DEVICE FOR DETECTING DEFECTS OF PATTERNS IN MICROELECTRONIC DEVICES

Publication

EP 0230285 B1 19911227 (EN)

Application

EP 87100518 A 19870116

Priority

- JP 839186 A 19860118
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Abstract (en)

[origin: EP0230285A2] An inspecting method and device for inspecting an object or objects (12, 14, 90) such as photomasks having a plurality of identical patterns (23), to detect defects of the patterns, wherein the object is placed such that the patterns lie in the same plane, and an inspection mask (20, 92) having a plurality of translucent apertures (26) is placed such that the inspection mask is adjacent and parallel to the object. The inspection mask and the object are moved relative to each other whereby each aperture is positioned opposite to mutually corresponding portions (24) of the patterns. The object and inspection mask are irradiated with rays of light emitted in a direction substantially normal to the plane of relative movements thereof. The rays of light transmitted through the apertures and the object are converted into electric signals, and the electric signals associated with the corresponding portions (24) of the patterns. If the electric signals of the corresponding portions of the patterns from each other, these portions are determined to be defective.

IPC 1-7

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IPC 8 full level

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